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AZ® P4000 Series Photoresists

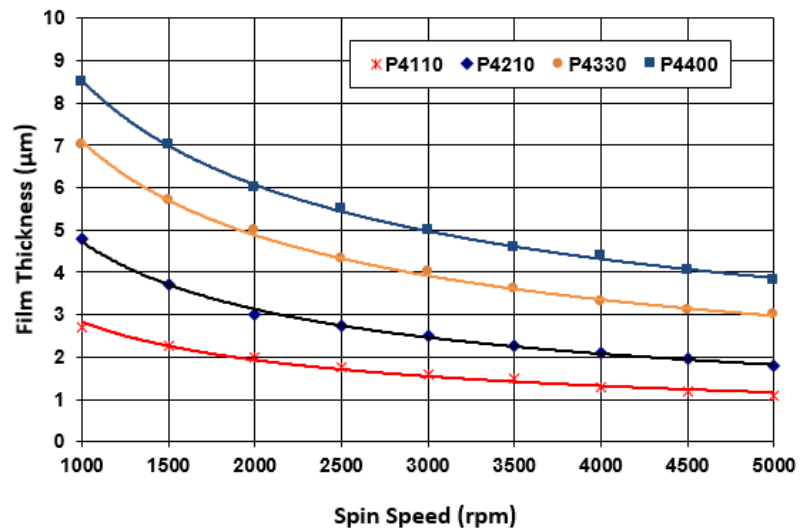


AZ P4000 Series Photoresists are general purpose i-line/h-line/g-line sensitive materials engineered for performance in most electro-plating and other metal deposition process environments. AZ P4000 resists exhibit excellent adhesion to metal seed layers and compatibility with nearly all plating solutions including gold-cyanide. Plating bath lives are maximized thanks to P4000's unique PAC chemistry which prevents leaching of the DNQ. Coated thickness range is approximately 1.0 to 9 μ m (single coat). Optimized for the AZ 400K developers (AZ 400K 1:4 or AZ 400K 1:3) or AZ 421K developer. MIF developers not recommended.

Items in this series:

- AZ P4110 Photoresist (Quart)
- AZ P4110 Photoresist (Gallon)
- AZ P4210 Photoresist (Quart)
- AZ P4210 Photoresist (Gallon)
- AZ P4330 Photoresist (Quart)
- AZ P4330 Photoresist (Gallon)
- AZ P4400 Photoresist (Quart)
- AZ P4400 Photoresist (Gallon)
- AZ P4620 Photoresist (Quart)
- AZ P4620 Photoresist (Gallon)
- AZ P4903 Photoresist (Gallon)

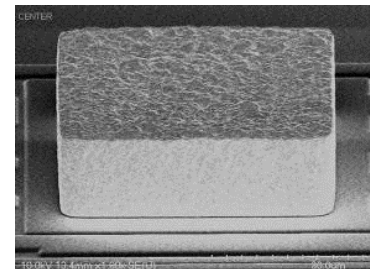
AZ® P4000 Series Spin Curves



100mm Si Wafers

Typical Process

Soft Bake: 110C
 Expose: g/h/i-line
 Post Expose Bake: Optional
 Develop: spray/immersion
 Develop: AZ 400K 1:3 or
 AZ 400K 1:4



90 μ m Au bump plated in P4620
 28 μ m resist film thickness
 Cyanide Gold Plating Solution

[I would like more information
about AZ P4000 Series
Photoresists!](#)

Authorized Distributor

**EMD
PERFORMANCE
MATERIALS**

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